# Effects of Alkali-PDT on Low Bandgap (Ag,Cu)InSe<sub>2</sub> Solar Cells

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### Motivation

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- □ Interest in CIGS to be a bottom cell in a tandem
- Reduced Ga/(Ga+In) (GGI) is required to lower the bandgap (*E*<sub>g</sub>)
  - But lower efficiencies obtained with E<sub>g</sub> < 1.1 eV</p>
- What approaches will improve efficiency of low E<sub>g</sub> CIGS?







### Approach 1: Ag Alloying

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- Lower defect density (Erslev et al. 2011)
- Longer minority carrier lifetime (Garris et al. 2017)
- Larger grain sizes (Chen et al. 2014)
- Improved long wavelength QE in low E<sub>g</sub> devices (Valdes et al. 2019)



N. Valdes et al., Sol. En. Mater. Sol. Cells, 2019.

ACIGS







L. Chen et al., IEEE J. Photovoltaics, 2014.





### Approach 2: Alkali Post-Deposition Treatments

- Led to record efficiency CIGS solar cells
- Most PDT studies done on co-evaporated CIGS, with GGI = 0.2 – 0.4
  - > We've focused on:
    - Will the PDT results apply for GGI = 0 (CIS)?
    - The effect of Ag on PDT for interest in Ag alloyed CIS and CIGS

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Solar Frontier Achieves World Record Thin-Film Solar Cell





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  - > We've focused on:
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How do Ga and Ag influence the alkali-PDT on CuInSe<sub>2</sub>?





### **Experimental Details**

Use three-stage co-evaporation to grow the following absorber layers:



Samples with alkali-PDT: ~7.5 nm KF or RbF with  $T_{sub} = 350^{\circ}C$  with Se flux

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Compare samples rinsed vs. not rinsed with deionized water





#### How does Ga influence the KF-PDT on CuInSe<sub>2</sub>?





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N. Valdes et al., *IEEE JPV*, p1846, 2019.

- Use XPS to understand differences in surface chemistry between CIGS+KF and CIS+KF
- □ F 1s spectra provides information on:
  - Intermediate chemistry after PDT and before CdS deposition
  - Proportional to K content without overlapping Auger lines







N. Valdes et al., IEEE JPV, p1846, 2019.

- Nearly identical F 1s peaks in nonrinsed CIS+KF and CIGS+KF
  - Ga does not affect KF content
  - Also see a similar intensity comparison in K 2p
- □ F 1s removed with water rinsing
  - F is on the surface as a watersoluble compound







N. Valdes et al., IEEE JPV, p1846, 2019.

Candidate	Binding Energy (eV)	
Measured F 1s	685.0	
GaF <sub>3</sub>	685.7	
InF <sub>3</sub>	685.0	
KF	684.0	
CuF <sub>2</sub>	684.3	

- M. Tabbal et al., Mat. Res. Soc. Symp. Proc., 1992.
- Y. Kawamoto et al., J. Fluorine Chem., 1999.
- W. Morgan et al., J. Am. Chem. Soc., 1973.
- S. Gaarenstroom and N. Winograd, J. Chem. Phys., 1977.







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# Ga $2p_{3/2}$ of CIGS+KF



N. Valdes et al., *IEEE JPV*, p1846, 2019.

- □ Ga  $2p_{3/2}$  narrows after rinsing
  - High GGI before rinsing
    - Baseline value afterwards
  - Removal of Ga with water rinsing

Туре	GGI
Non-rinsed	0.47
Rinsed	0.28











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# Ga $2p_{3/2}$ of CIGS+KF



- Low binding energy peak: Ga in CIGS
  - Matches CIGS+KF rinsed and CIGS
- □ High binding energy peak: GaF<sub>3</sub>
  - > Also seen by Lepetit et al. in 2017

Туре	Binding Energy (eV)
Measured GaF <sub>3</sub>	1119.0
Literature GaF <sub>3</sub>	1119.4

M. Tabbal et al., Mat. Res. Soc. Symp. Proc., 1992.





# In $3d_{5/2}$ CIGS+KF

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N. Valdes et al., *IEEE JPV*, p1846, 2019.

- Rinsed samples have higher intensity In 3d peaks
  - Surface layer that reduced XPS signal removed by water rinsing
    - Other elements' spectra also show this

□ CIGS+KF does not show InF<sub>3</sub> peak





# In 3d<sub>5/2</sub> of CIS+KF and CIGS+KF

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- CIGS+KF does not show InF<sub>3</sub> peak
- CIS+KF rinsed similar to CIGS+KF rinsed





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- CIS+KF rinsed similar to CIGS+KF rinsed
- CIS+KF non-rinsed shows peak at higher binding energy









N. Valdes et al., *IEEE JPV*, p1846, 2019.







# In $3d_{5/2}$ of CIS+KF

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N. Valdes et al., *IEEE JPV*, p1846, 2019.

□ Low binding energy peak: In in CIS

Matches CIS+KF rinsed and CIS

□ High binding energy peak: InF<sub>3</sub>

Туре	Binding Energy (eV)	
Measured $InF_3$	445.9	
Literature InF <sub>3</sub>	446.0	

• T. Paul and D. Bose, J. Appl. Phys., 1991.





# In 3d<sub>5/2</sub> of CIS+KF and CIGS+KF

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N. Valdes et al., *IEEE JPV*, p1846, 2019.

- $\Box$  InF<sub>3</sub> appears in CIS+KF non-rinsed
  - But not in CIGS+KF non-rinsed
- □ Preferential reaction:
  - F binds to In in CIS+KF
  - F binds to Ga in CIGS+KF





# Role of $GaF_3$ and $InF_3$ on Non-Rinsed Films



□ GaF<sub>3</sub> or InF<sub>3</sub> are products of KF reaction with Cu-deficient CIGS

- > Could be  $K(In,Ga)F_4$  and  $K_3(In,Ga)F_6$  (exist, but no XPS information found)
- □ GaF<sub>3</sub> or InF<sub>3</sub>  $\rightarrow$  no effect on performance as they are removed during CdS deposition
- □ Not clear if removal of surface Ga via GaF<sub>3</sub> alters surface electronic properties





### Cu Composition Reduction Due to KF-PDT

Туре	% Reduction Cu 2 <i>p</i> XPS Peak Area
$CIS \rightarrow CIS + KF$	35
$CIGS \rightarrow CIGS + KF$	51

Samples were water rinsed. N. Valdes et al., *IEEE JPV*, p1846, 2019.

- Alkali-PDTs known to reduce Cu content on the surface
- Ga containing films have larger decrease in surface Cu concentration due to KF

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- > Is it due to Ga chemistry, or a morphology effect?
- > Might explain "depletion" in surface Cu with KF







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- KF shows similar  $V_{OC}$  trends with or without Ga
  - > Focus on low  $E_a$  case, CIS
- Baseline CdS (50 nm):
  - > CIS and CIS+KF  $\rightarrow$  Similar  $V_{OC}$
- Thin CdS (35 nm):
  - > Reduced  $V_{\rm OC}$  in CIS
  - > No  $V_{\rm OC}$  reduction in CIS+KF
    - Improved CdS growth

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N. Valdes et al., IEEE JPV, p906, 2019.



# KF Effect on CIS $V_{OC}$ After Heat Treatment



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- Some devices received 2 min. 200°C heat treatment in air after initial test
- All types get V<sub>OC</sub> boost except CIS with thin CdS
- □ CIS+KF with thin CdS:  $V_{\text{OC}}$  > 500 mV
- Heat treatment critical for high efficiency CIS+KF



### High Efficiency CIS+KF



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- Deposited MgF<sub>2</sub> anti-reflection coating on best cells
- Best cell η = 16.0%
  - Record CuInSe<sub>2</sub> solar cell
- □ KF → higher efficiency CIGS for range of Ga content

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Are high efficiencies also possible in ACIS+KF?



# V<sub>OC</sub> Comparison



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- □ ACIS has lower  $V_{\rm OC}$  than CIS
  - Low carrier concentration in best devices
  - But makes up for V<sub>OC</sub> reduction by improved current collection (Valdes et al. 2019)

Baseline CdS. Devices were not heat treated. N. Valdes et al., *IEEE JPV*, p906, 2019.





# V<sub>OC</sub> Comparison



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- □ ACIS+KF has very low  $V_{\rm OC}$
- V<sub>OC</sub> reduction independent of KF thickness from 0.5 nm to 15 nm
- ❑ Uppsala U. → reduced KF amounts required in ACIGS (Edoff et al. 2017, Donzel-Gargand et al. 2018)

Baseline CdS. Devices were not heat treated. N. Valdes et al., *IEEE JPV*, p906, 2019.





# V<sub>OC</sub> Comparison

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### Group 1 Composition Reduction Due to KF by XPS

Туре	Element	% Reduction XPS Peak Area
$CIS \rightarrow CIS + KF$	Cu	35
$ACIS \to ACIS+KF$	Cu	42
$ACIS \to ACIS+KF$	Ag	25

Samples were water rinsed. N. Valdes et al., *IEEE JPV*, p1846, 2019.

- □ Ag decreases less than Cu with KF-PDT
  - > Also seen by Donzel-Gargand et al. 2018 in ACIGS
- Additional observations by XPS for ACIS and ACIGS:
  - > No change in surface K or F content or binding energy
  - >  $InF_3$  in ACIS+KF and  $GaF_3$  in ACIGS+KF still present in non-rinsed samples





### Raman Spectroscopy of Bare Absorber Layers



N. Valdes et al., IEEE JPV, p906, 2019.

- □ Broad peak ~255 cm<sup>-1</sup> for ACIS+KF
- Not identified by Raman or GIXRD
- Possible candidates:
  - $\succ$  α-ln<sub>2</sub>Se<sub>3</sub> = 255 cm<sup>-1</sup>
  - >  $Cu_2Se = 260 \text{ cm}^{-1}$
- Regardless, different surface exists for ACIS+KF
- Still present after water rinse or chemical etch
  - ➢ e.g. HCI, KCN, NH₄OH





### Features of ACIS+KF Devices

□ ACIS+KF demonstrates lower  $E_a$  compared to other devices

Interface recombination dominates in these devices

□ Light to dark crossover observed in *J*-*V* of ACIS+KF

> Maybe related to photoconductivity in the CdS layer







# Comparison of Best Cell Baseline vs. Thin Buffers

Туре	Baseline CdS V <sub>oc</sub> (mV)	Thin CdS <i>V<sub>oc</sub> (</i> mV)	Thin - Baseline V <sub>OC</sub> (mV)
CIS	482	469	- 13
CIS+KF	485	487	+ 2
ACIS	455	458	+ 3
ACIS+KF	411	436	+ 25

Reduced CdS thickness:

Devices were not heat treated N. Valdes et al., *IEEE JPV*, p906, 2019.

- > CIS has decreased  $V_{OC}$  likely due to incomplete CdS coverage
- > No change in  $V_{OC}$  for CIS+KF or ACIS
- > Large improvement in  $V_{OC}$  in ACIS+KF





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- Large improvement in V<sub>oc</sub> in ACIS+KF

Does CdS grow differently due to KF and/or Ag alloying?



### SEM with 10 nm CdS Overlayer

CIS



- □ Incomplete coverage on some grains
  - Related to {112} oriented grains (Witte et al. 2013)
  - Metal or anion terminated

CIS+KF



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Improved coverage due to KF



N. Valdes et al., IEEE JPV, p906, 2019.



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### SEM with 10 nm CdS Overlayer

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#### ACIS



- □ Large grains with incomplete coverage
  - Perhaps same as CIS but on a larger scale

ACIS+KF



- Complete coverage even with 10 nm CdS
  - Increased Cd and S seen by XPS (Valdes et al. 2019)

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□ KF causes different nucleation



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Do we see similar trends with RbF-PDT?

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### How Do Best Cell Results Compare with RbF?

Туре	Baseline CdS V <sub>oc</sub> (mV)	Thin CdS V <sub>oc</sub> (mV)	Thin - Baseline V <sub>oc</sub> (mV)
CIS	482	469	- 13
CIS+RbF	482	477	- 5
ACIS	455	458	+ 3
ACIS+RbF	362	386	+ 24

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RbF J-V results  $\rightarrow$  similar trends to KF: 

Devices were not heat treated

- > CIS+RbF:
  - \* Comparable  $V_{OC}$  to CIS (with no heat treatment)
  - Reduced  $V_{\rm OC}$  loss with thin CdS
- > ACIS+RbF:
  - $\diamond$  Decreased V<sub>OC</sub> vs. ACIS
  - \* Large increase in  $V_{OC}$  with thinner CdS





### Raman Spectra of Bare Absorber Layers



- Unidentified peak also exists in ACIS+RbF
  - Both KF and RbF lead to a modified surface in ACIS+alkali-PDT





# Summary (1/2)

- Investigated alkali-PDTs on CIS and the influence of Ga and Ag
- □ Studied the XPS properties of CIS vs. CIGS
  - ➢ Ga does not change the amount of K or F on surface
  - Group III fluorides are products of KF reaction
  - Preferential reaction occurs in which
    - $\textbf{\& CIGS+KF} \rightarrow \text{GaF}_3$
    - $\textbf{\& CIS+KF} \rightarrow \text{InF}_3$
  - CIGS has larger decrease in Cu on surface after KF
- □ CIS+KF devices:
  - Tolerate reduced CdS thickness
  - > Have high efficiencies after heat treatment
    - \*  $\eta$  = 16.0% for CIS without Ga





# Summary (2/2)

- □ ACIS+KF leads to devices with low  $V_{OC}$
- □ ACIS+KF has properties unique from other absorbers in this work:
  - Less Ag reduction at surface compared with Cu
  - ➢ Unidentified peak at 255 cm<sup>-1</sup> in Raman spectra
  - Dominant interface recombination
  - Light to dark crossover
  - Different CdS growth
- □ RbF-PDT gives similar *J*-*V* and Raman results for both CIS and ACIS





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